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ICPT Announces 2017 CMP Lifetime Achievement Award Winners

Three individuals were recognized for their achievements in the field of semiconductor planarization technology at the 2017 International Conference on Planarization/CMP Technology held October 11-13 in Leuven, Belgium. The awardees are Prof. S.V. Babu of Clarkson University; Prof. Jin-Goo Park of Hanyang University; and Dr. Gerfried Zwicker of the Fraunhofer Institute for Silicon Technology.

Prof. S.V. Babu joined the faculty at Clarkson in 1981 and began his research programs on CMP following an invited guest lecture by Drs. Michael Fury and Frank Kaufman of IBM in 1992. The program has flourished under his direction, with over $5M in research funding from CMP suppliers and end users. For more than twenty years he has organized the Lake Placid CAMP (Center for Advanced Materials Processing) CMP conferences which are recognized as one of the premiere forums for advanced CMP research issues. Dr. Babu has published over 270 papers in journals and conference proceedings, is the author of 31 patents, and has co-edited four books. Most of his published work is in the area of CMP. He is also the recipient of several industry and academic honors, including being named a Distinguished Professor at Clarkson University in 2004.

Prof. Jin-Goo Park joined the faculty at Hanyang University in 1994 after starting his career at Texas Instruments in Dallas where he was responsible for microcontamination control in semiconductor wet processing. Dr. Park is currently a professor in the Department of Materials Engineering as well as Director of the Micro Biochip Center and Nano-bio Electronic Materials and Processing Lab. He has authored more than 500 technical publications and presentations in the areas of wafer cleaning, CMP and nano-bio MEMS. Dr. Park is a founding member and current President of ICPT.

Dr. Gerfried Zwicker has been conducting research in semiconductor processing technology for more than 30 years, first in plasma etch processes then moving on to CMP where he has spent most of his career. He is head of the CMP group at the Fraunhofer Institute for Silicon Technology (ISIT) in Itzehoe, Germany. Nearly 20 years ago, Dr. Zwicker founded the German CMP users group which evolved into the European CMP users group which continues to hold meetings every six months on topics related to CMP technology. His research has focused on general CMP process development as well as specific processes for high power devices and for special applications such as MEMS. Dr. Zwicker sits on the Executive Committee of ICPT.

The first ICPT Lifetime Achievement Award was granted to Dr. Klaus Beyer of IBM in 2015. In the mid 1980's, Dr. Beyer invented chemical mechanical planarization (CMP) while working on the cleaning of Si and oxide surfaces at IBM. He decided to try an adapted polishing technique to remove unwanted mounds of oxide after a reflow step and the result was a scratch-free planarized oxide surface. This was the first instance of CMP as it is known today. The ICPT conference is hosted on a rotating basis among six international CMP Users Groups in Europe, Japan, Korea, Taiwan, China, and the USA. Next year's ICPT will be held in Seoul, South Korea, and welcomes anyone interested in learning more about current issues in the field of CMP technology.